# Mixed-Mode Device/Circuit Simulation



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### **Outline**

Circuit simulation and compact models

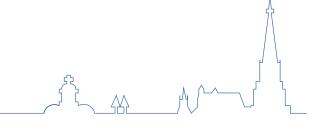
Numerical models instead of compact models

Challenges in numerical modeling

Mixed-mode device/circuit simulation

**Examples** 

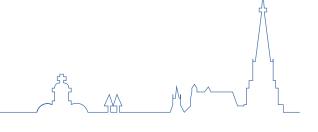
Conclusion



### Circuit simulation fundamental

Development of modern IC

To understand and optimize the way a circuit works



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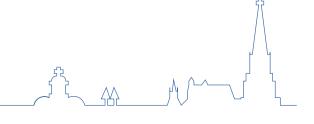
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Lumped elements: R, C, L, etc.

Current and voltage sources, controlled sources

Semiconductor devices

Thermal equivalent circuit (coupling and self-heating)



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Characterized by coupled partial differential equations



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## For the simulation of large circuits we need compact models

Obtained from simplified solutions of these PDEs or empirically Must be very efficient (compact!)



# **Compact Modeling**

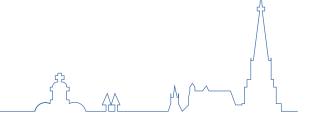
### Derivation of compact models based on fundamental equations

Often the drift-diffusion framework is used

Simplifying assumptions on geometry, doping profiles, material parameters

 $\Rightarrow$  Compact model

It is becoming increasingly difficult to extract main features



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Number of parameters

Physical meaning of these parameters

Predictiveness difficult to obtain, calibration required



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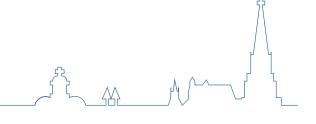
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## Compact modeling challenges (ITRS)

Quantum confinement

Ballistic effects

Inclusion of variability and statistics



# **Simulation with Compact Models**

## Advantages of using compact models

Very fast execution (compared to PDEs)



## Simulation with Compact Models

### Advantages of using compact models

Very fast execution (compared to PDEs)

### Disadvantages

Many parameters

Physically motivated parameters

Fit parameters

Parameter extraction can be quite cumbersome

Device optimization via geometry and doping profile hardly possible

Considerable model development effort

Limited model availability (DG, TriGate, FinFETs, GAAFETs, etc.)

Scalability questionable

Quantum effects

Non-local effects



## **Mixed-Mode Simulation**

#### Instead of

Analytical expressions describing the device behavior (compact models)

Rigorous device simulation based on

Coupled partial differential equations!



# **Compact Modeling – Numerical Modeling**

### Advantages of numerical device simulation

Fairly arbitrary devices (doping, geometry)

Realistic doping profiles from process simulation

Natural inclusion of

2D/3D effects

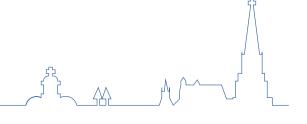
Non-local effects (via appropriate transport model)

Quantum mechanical effects (via simplified model or Schrödinger's equation)

Temperature dependencies

Sensitivity of device/circuit figures of merit to process parameters

Better predictivity for scaled/modified devices



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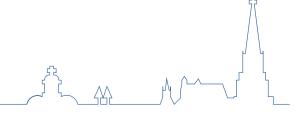
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### Disadvantages of numerical modeling

Performance (don't compare!)

Convergence sometimes costly/difficult to obtain

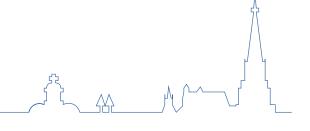
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Ballistic effects become important

No ballistic transistor in sight, but still important effect



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Transport remains classical Critical gate length aroung 10 nm

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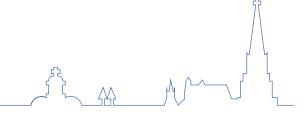
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### Exploitation of new effects

Strain effects used to boost mobility

Substrate orientation and channel orientation



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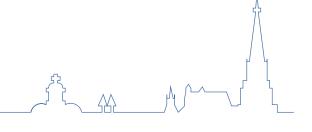
### Exploitation of new materials

Strained silicon, SiGe, Ge, etc. High-k dielectrics



## Classical transport described by Boltzmann's equation

Allows inclusion of sophisticated scattering models, quasi-ballistic transport

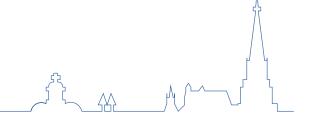


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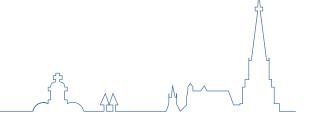
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Simplest moment-based model: the classic drift-diffusion model

$$\epsilon \nabla^2 \psi = q(n - p - C)$$

$$\nabla \cdot (D_n \nabla n - n \mu_n \nabla \psi) - \frac{\partial n}{\partial t} = R$$

$$\nabla \cdot (D_p \, \nabla p + p \, \mu_p \, \nabla \psi) \, - \frac{\partial p}{\partial t} = R$$

Requires models for physical parameters D,  $\mu$ , and R

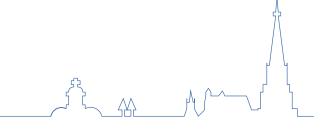
These models capture fundamental physical effects

Velocity saturation, SRH recombination, impact-ionization

Models can be quite complex

Used to be basis for the derivation of compact models

Drift-diffusion model inaccurate for short-channel devices



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Higher-order moment models available

Comparison of scaled DG-MOSFETs

Comparison with fullband Monte Carlo data Transport parameters from FBMC



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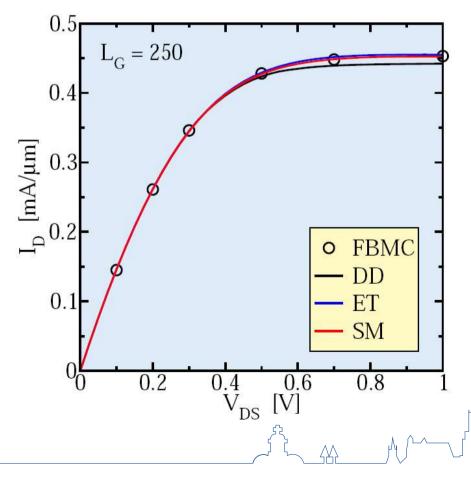
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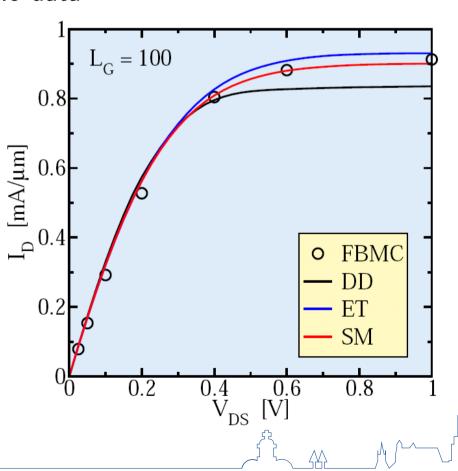
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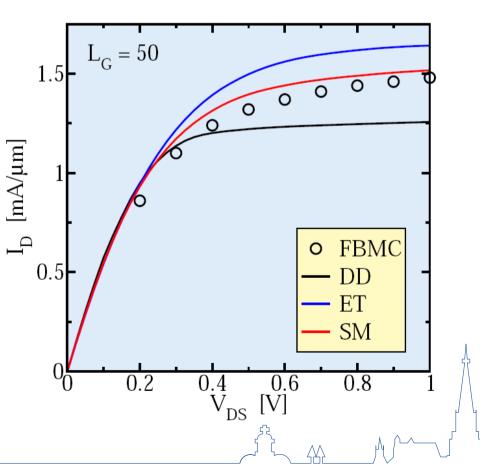
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SM accurate at  $50 \, \mathrm{nm}$ Non-Maxwellian effects
Low computational effort
'TCAD' compatible



### **Mixed-Mode Simulation**

### Simulator coupling

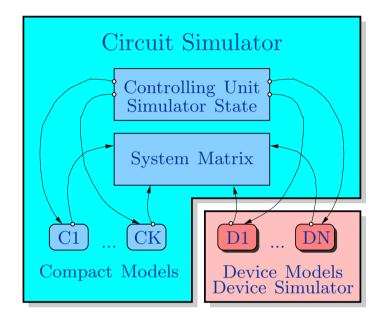
Simple, straight forward solution

Two-Level Newton algorithm

Spice-like damping algorithms usable

Many iterations for device equations needed

Parallelization straight-forward





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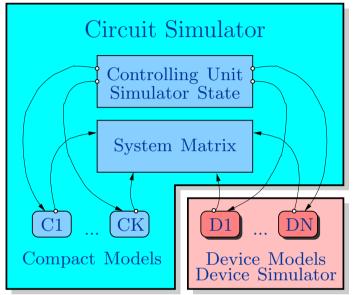
## All-In-One solution (Full-Newton)

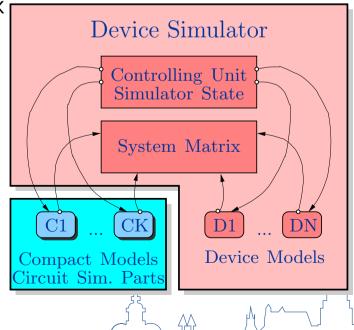
Circuit and device equations in one single matrix

Full-Newton algorithm

Complex convergence behavior

Parallelization more complicated





#### Two-Level Newton

Device simulator is called for each circuit iteration

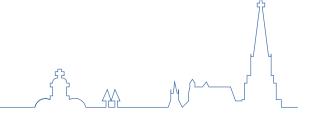
Fixed set of contact voltages

Contact current response  $I_{
m C}^k$ 

Problematic:  $g_{\mathrm{eq}}^k = \frac{\partial I_{\mathrm{C}}}{\partial V_{\mathrm{C}}}|_k$ 

Device simulator iterates until convergence

Last iteration as initial-guess Linear prediction algorithm



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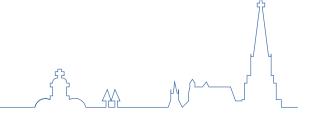
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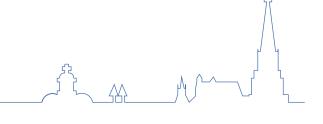
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### Advantages

Straight-forward parallelization

Spice-like damping schemes can be applied

Stable operating point computation



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### Disadvantages

Considerable overhead



## **Full-Newton Approach**

## Device and circuit equations in one matrix

Simultaneous damping of device and circuit equations



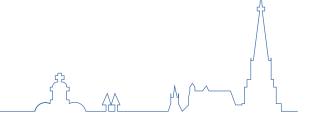
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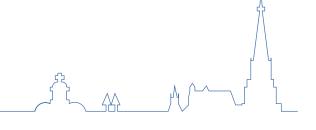
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Quadratic convergence properties for a good initial-guess (fast!)

Initial-guess hard to construct

Damping schemes



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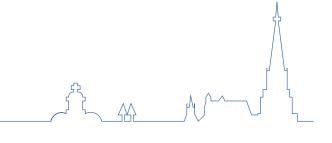
## Reliable DC operating point calculation of utmost importance

Drift-diffusion solution as initial-guess for Higher-order transport models Electro-thermal solution

Transient simulations better conditioned



Why is convergence hard to obtain?



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Conventional boundary condition for numerical devices

 $V_{\mathrm{C},i}$  (device contact potential) =  $\varphi_{\mathrm{C},i}$  (node voltage)

Carrier concentrations depend exponentially on the potential



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Current flowing out of the contact affects node voltages

System is extremely unstable at the beginning of the iteration

Similar situation as with current boundary condition

Shifts in the DC offset require many iterations Distributed quantities provide 'internal state'



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## Alternative boundary condition for numerical devices

$$V_{\mathrm{C},i}=arphi_{\mathrm{C},i}-V_{\mathrm{ref}}$$
 with  $V_{\mathrm{ref}}=rac{1}{N_{\mathrm{c}}}\sum_{j}arphi_{\mathrm{C},j}$  (average potential)

Average potential changes during the iteration and operation

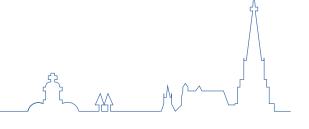


# **Convergence – Damping Schemes**

## Simple Methods

Limitation of node voltage update to  $2V_{\mathrm{T}}$   $\mathit{Many\ iterations\ needed}$ 

Initial guess close to the solution (experimental value:  $\pm 0.2 \text{ V}$ )



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#### Traditional device simulation methods

Damping after Bank and Rose (SIAM 1980)  $\overline{MINIMOS}$  damping scheme

Standard damping schemes not suitable for mixed-mode problems



# **Convergence – Embedding Scheme**

# Shunt an iteration dependent conductance $G_{ m S}^k$ at every contact

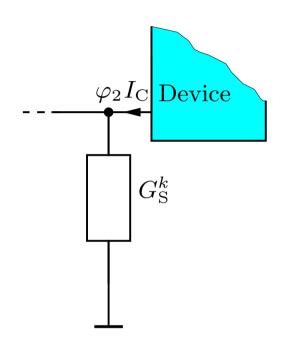
Purely empirical expression

$$G_{\rm S}^k = \max \left( G_{\rm min}, \ G_0 \times 10^{-k/\kappa} \right)$$

$$G_0 = 10^{-2} \,\mathrm{S}$$

$$G_{\rm min} = 10^{-12} \,\mathrm{S}$$

$$\kappa = 1.0 \ldots 4.0$$





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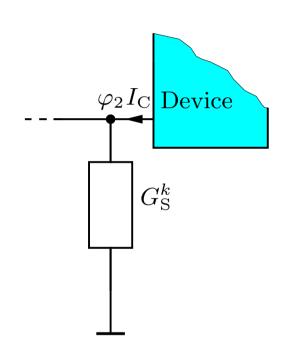


Zero initial-guess for node voltages

Charge neutrality assumptions for semiconductor devices

Convergence within 20–50 iterations

Comparable to SPICE with compact models



# **Examples**

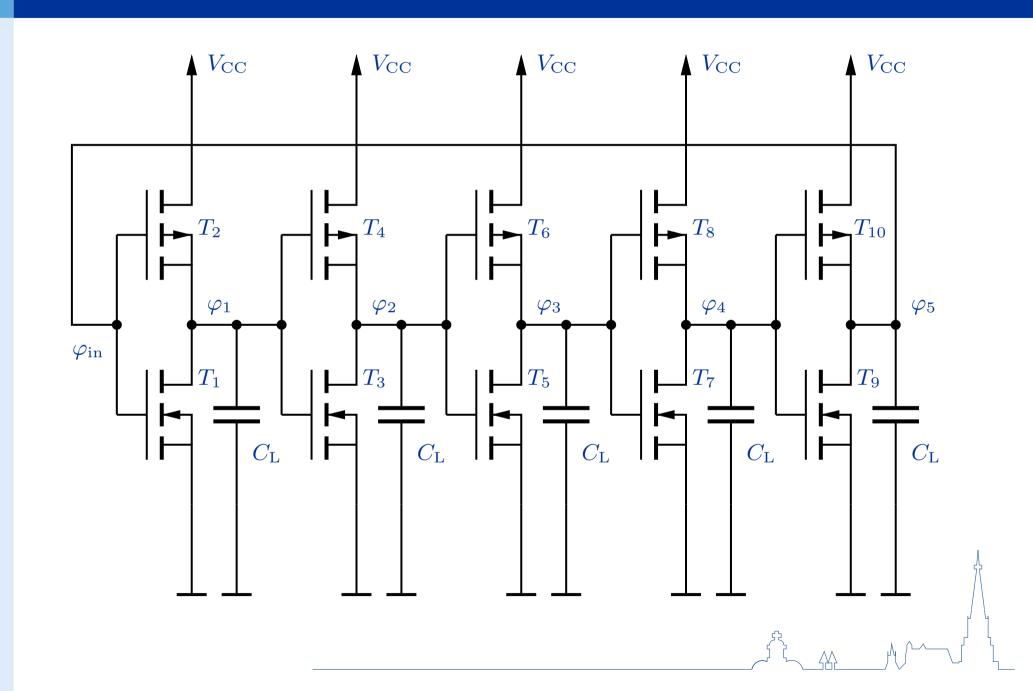
Five-stage CMOS ring oscillator

Long-channel/short-channel behavior

Electro-thermal analysis of an operational amplifier ( $\mu$ A709)



# Five-Stage CMOS Ring Oscillator

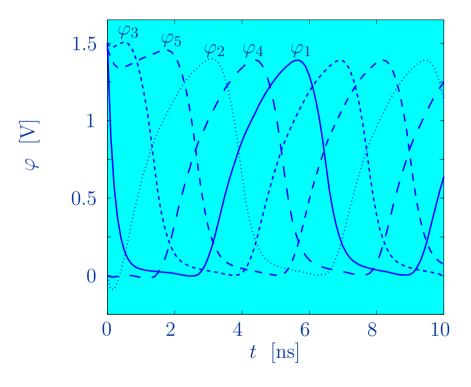


# **CMOS** Ring Oscillators

Long-channel devices ( $L_{\rm g}=2\,\mu{\rm m}$ )

First timestep:  $\varphi_{in} = 0 V$ 

Excellent agreement DD and ET Non-local effects negligible





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Short-channel devices ( $L_{
m g}=0.13\,\mu{
m m}$ )

Significant difference DD and ET

Non-local effects important

Larger currents for ET

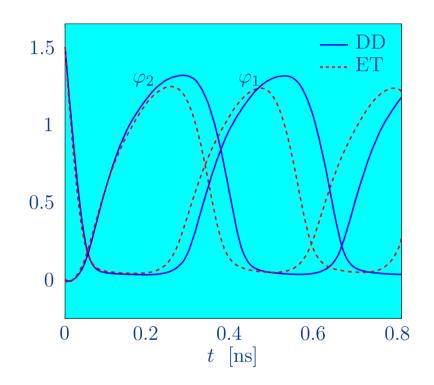
15% difference in delay time

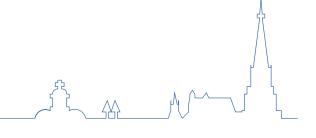
### Complexity of models can be increased

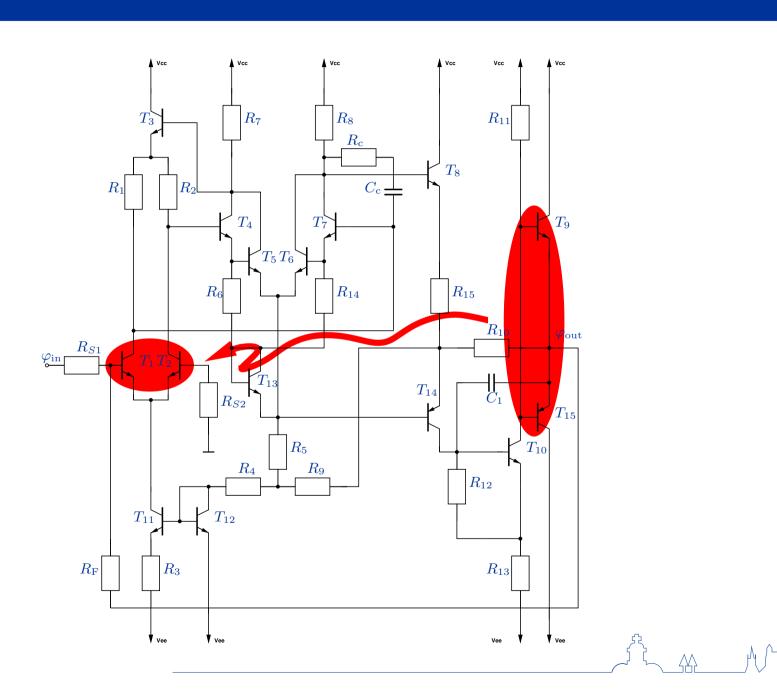
Higher-order transport models

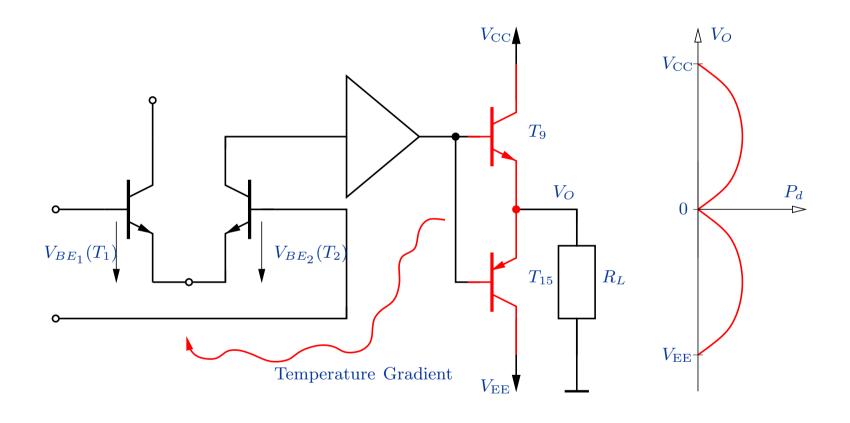
More accurate quantum corrections

Different mobility models











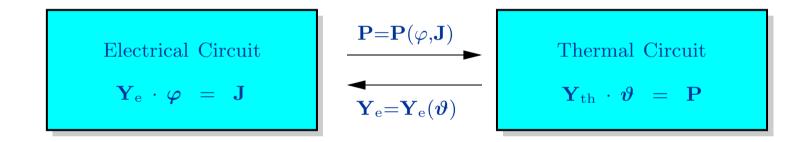
## **Thermal Circuit**

### Thermal coupling modeled via a thermal circuit

Thermal coupling between individual devices

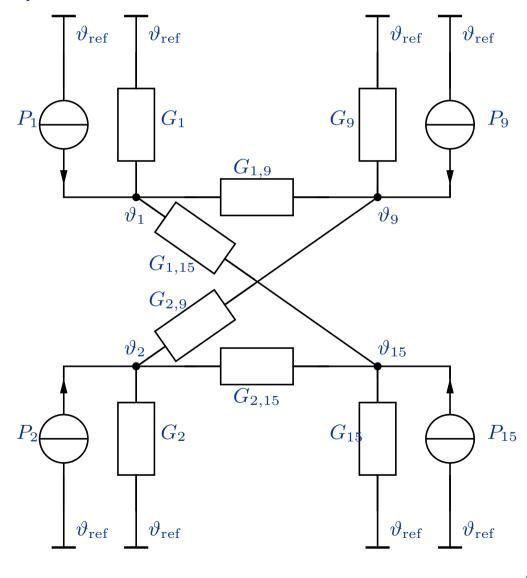
Thermal equations similar to Kirchhoff's equations

Formally derived from the discretized lattice heat-flow equation





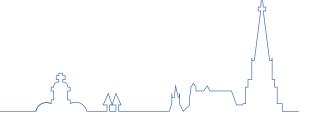
## Simple thermal equivalent circuit



#### Electrical simulation

All 15 transistors numerically simulated

System-size: 37177, simulation time: 1:08 hours (101 points, DC transfer)



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#### Electro-thermal simulation

Input and output stage with self-heating (4 Transistors)

Thermal coupling effects

Thermal feedback from the output to the input stage

Thermal interaction between all 4 transistors

Highly non-linear problem, complex convergence behavior

System-size: 40449, simulation time: 3:08 hours



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### Electro-thermal simulation with simplified self-heating model

Same coupling effects as before

Practically same results

System-size: 38477, simulation time: 1:22 hours

## DC Stepping

 $\mathsf{Gain} \approx 35000$ 

 $\Delta \varphi_{\mathrm{out}} = 0.7 \mathrm{\ V}$  (101 points)

Critical point 0 V

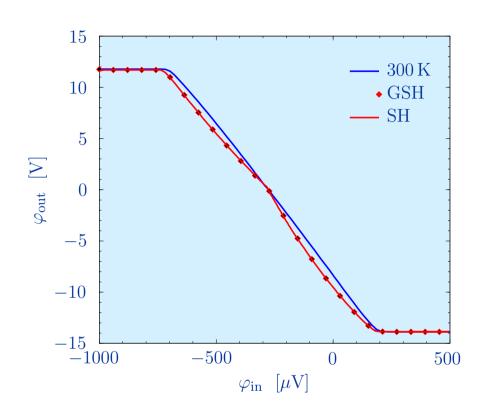
## Thermal feedback caused bumps

Input stage:  $\Delta T$ 

$$\Delta T \propto P$$

 $\max(\Delta T) = -22 \text{ mK}$ 

Input voltage difference



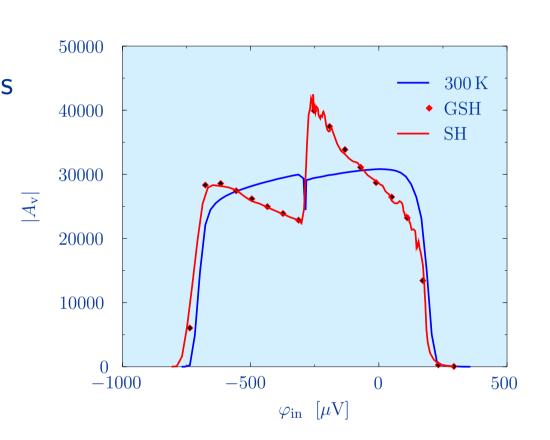


Open-loop voltage gain  $|A_v|$ Optimistic thermal conductances

Stronger impact published

 $|A_{
m v}|$  can even change sign

OpAmp can become unstable





#### **Conclusions**

For circuit design compact models are indispensable

Intermediate phase when devices structures is not established

Mixed-mode circuit/device simulation can be used

Motivation for mixed-mode device-circuit simulation

When compact models are inconvenient/not available

Verification of compact models in a more realistic environment

Optimization of devices

Exploitation of new device designs

Examples have been simulated with MINIMOS-NT

Go to http://www.iue.tuwien.ac.at and try it

